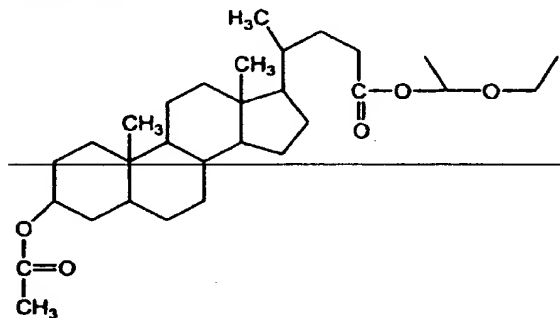


In the Claims:

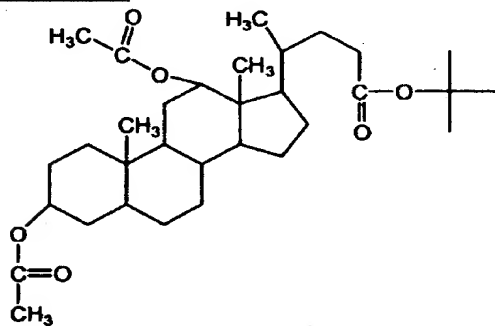
Please amend claims 1, 3 and 6, as follows:

Claim 1 (currently amended) An additive of following Formulas ~~3-7~~ 4 or 6 for a photoresist composition for a resist flow process:

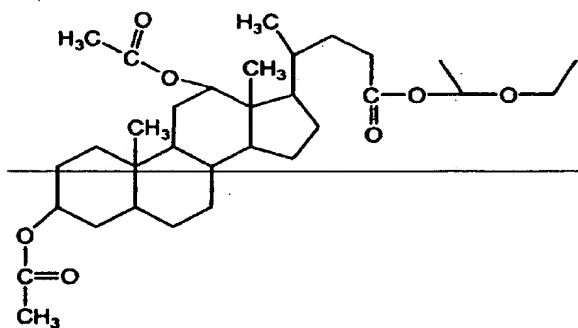
Formula 3



Formula 4



Formula 5



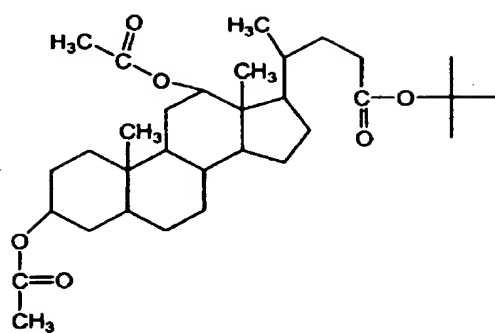
The chemical structure shows a steroid nucleus with four ester groups. At the 3-position, there is an acetate group (CH<sub>3</sub>-C(=O)-O-). At the 17-position, there is a 2-methylbutyrate group (CH<sub>3</sub>-CH<sub>2</sub>-CH(CH<sub>3</sub>)-C(=O)-O-). At the 20-position, there is an acetate group (CH<sub>3</sub>-C(=O)-O-). At the 21-position, there is an acetate group (CH<sub>3</sub>-C(=O)-O-). The steroid nucleus has methyl groups at the 10 and 13 positions.

The chemical structure shows a steroid nucleus with several modifications. At the 3-position, there is an acetate group ( $\text{CH}_3\text{COO}$ ). At the 10-position, there is a methyl group ( $\text{CH}_3$ ). At the 13-position, there is a methyl group ( $\text{CH}_3$ ). At the 14-position, there is a methyl group ( $\text{CH}_3$ ). At the 17-position, there is a side chain consisting of a methyl group ( $\text{CH}_3$ ), a methylene group ( $\text{CH}_2$ ), and a carbonyl group ( $\text{C=O}$ ) which is part of an ester linkage to a 2-ethoxyethyl group ( $\text{OCH}_2\text{CH}_2\text{OCH}_3$ ). At the 20-position, there is a methyl group ( $\text{CH}_3$ ). At the 21-position, there is a methyl group ( $\text{CH}_3$ ). At the 22-position, there is a methyl group ( $\text{CH}_3$ ). At the 23-position, there is a methyl group ( $\text{CH}_3$ ). At the 24-position, there is a methyl group ( $\text{CH}_3$ ). At the 25-position, there is a methyl group ( $\text{CH}_3$ ).

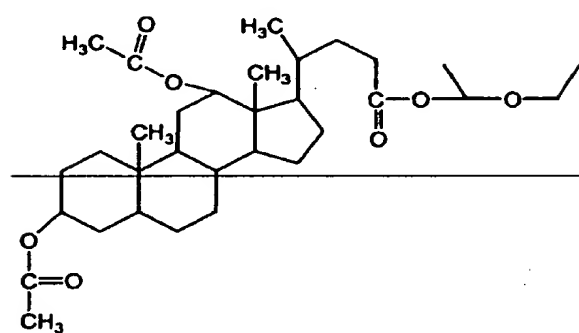
Claim 3 (currently amended) A photoresist composition comprising:  
a photoresist polymer, a photoacid generator, an additive of following  
Formulas 3-7 4 or 6, and an organic solvent,

CC(=O)Oc1ccc2c(c1)C(=O)O[C@H]3[C@@H](OC(=O)C)C[C@H]4[C@@H](C)C[C@H](C)[C@H]34

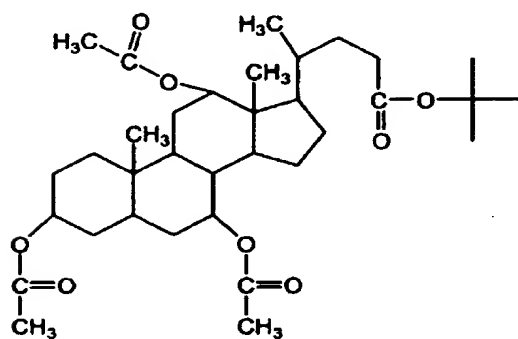
Formula 4



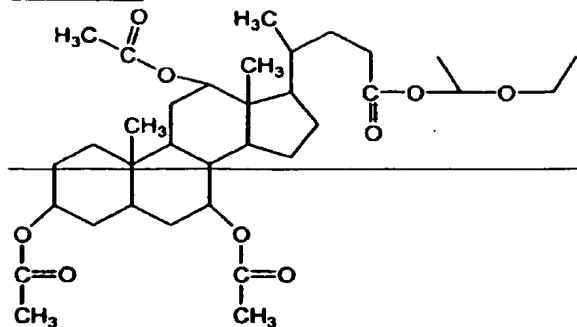
Formula 5



Formula 6



Formula 7

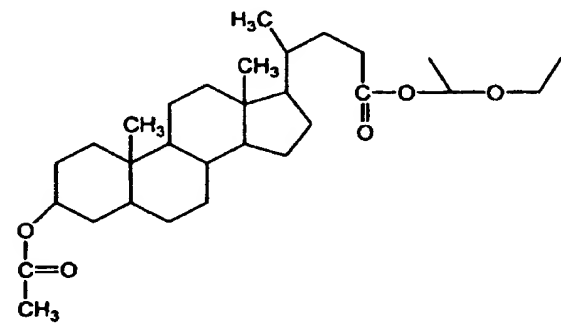


Claims 4-5 (previously canceled)

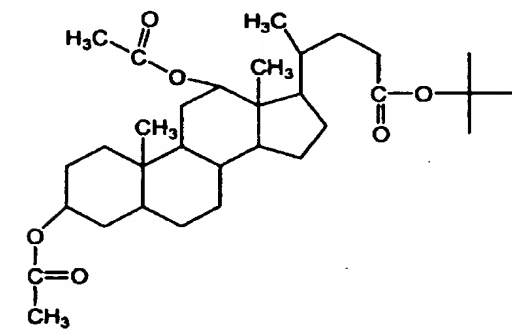
Claim 6 (currently amended) ~~The photoresist composition of claim 3~~ A photoresist composition comprising:

a photoresist polymer, a photoacid generator, an additive of following Formulas 3-7 and an organic solvent.

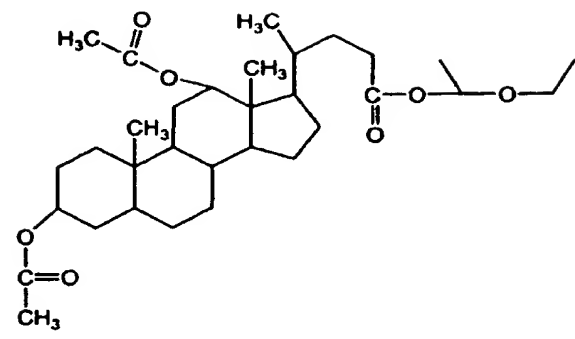
Formula 3



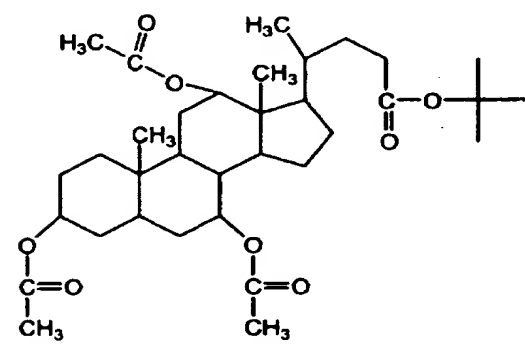
Formula 4



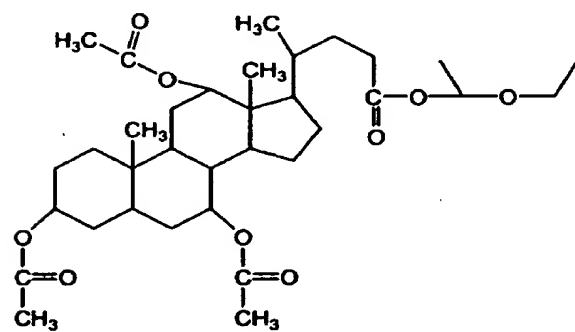
Formula 5



Formula 6



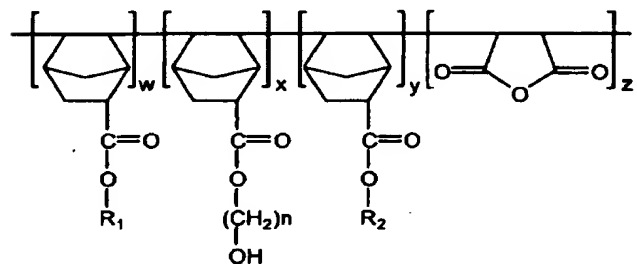
Formula 7



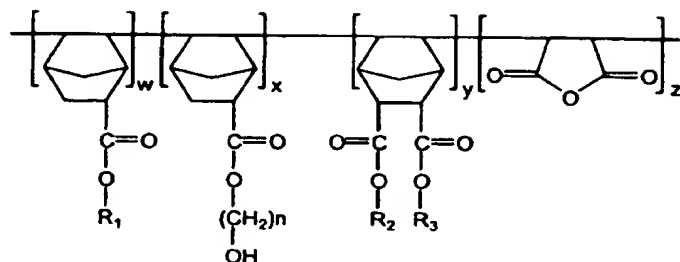
; and

wherein the photoresist polymer is a compound of following Formulas 8 or 9:

Formula 8



Formula 9



wherein,  $R_1$  is an acid labile protecting group;

$R_2$  is hydrogen;

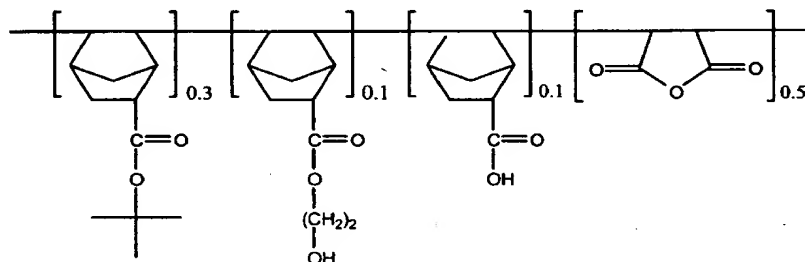
$R_3$  is hydrogen, selected from the group consisting of  $C_1$ - $C_{10}$  alkyl,  $C_1$ - $C_{10}$  alkoxyalkyl, and  $C_1$ - $C_{10}$  alkyl containing at least one hydroxyl group (-OH);

$n$  is an integer from 1 to 5; and

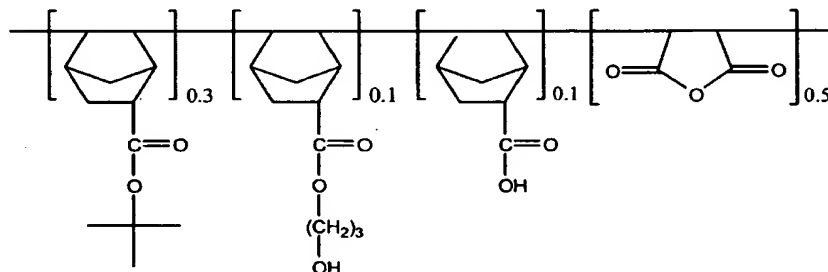
$w$ ,  $x$ ,  $y$  and  $z$  individually denote the mole ratio of each monomer, preferably with proviso that  $w + x + y = 50\text{mol}\%$ , and  $z$  is  $50\text{mol}\%$ .

Claim 7 (previously amended) The photoresist composition of claim 6 wherein the photoresist polymer is selected from the group consisting of compounds of following Formulas 10 to 13:

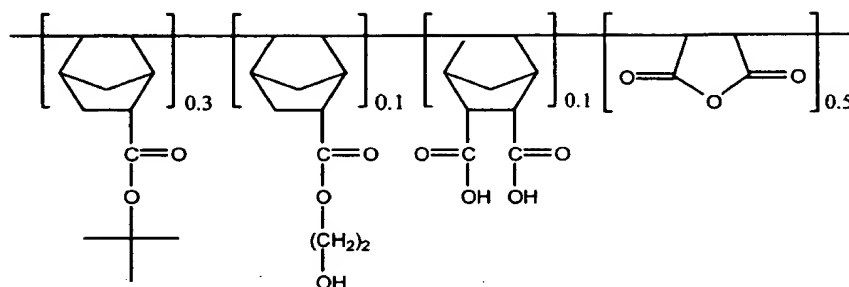
Formula 10



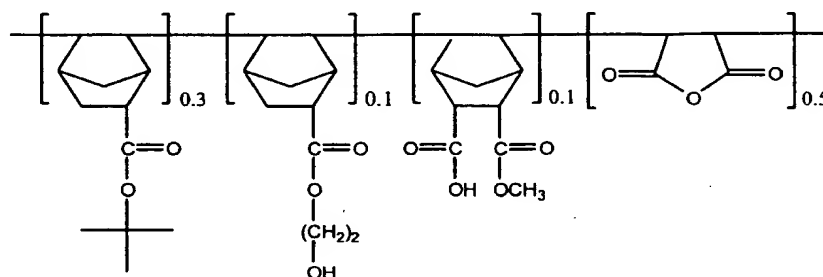
Formula 11



Formula 12



Formula 13



Claim 8 (original) The photoresist composition of claim 3 wherein the additive is present in an amount ranging from about 1 to about 70% by weight of the photoresist polymer.

Claim 9 (original) The photoresist composition of claim 3 wherein said photoacid generator is selected from the group consisting of diphenyl iodide hexafluorophosphate, diphenyl iodide hexafluoroarsenate, diphenyl iodide hexafluoroantimonate, diphenyl p-methoxyphenyl triflate, diphenyl p-toluenyl triflate, diphenyl p-isobutylphenyl triflate, diphenyl p-tert-butylphenyl triflate, triphenylsulfonium hexafluorophosphate, triphenylsulfonium hexafluoroarsenate, triphenylsulfonium hexafluoroantimonate, triphenylsulfonium triflate, dibutylnaphthylsulfonium triflate, and mixtures thereof.

Claim 10 (original) The photoresist composition of claim 3 wherein the photoacid generator is present in an amount ranging from about 0.01 to about 10% by weight of the photoresist polymer.

Claim 11 (original) The photoresist composition of claim 3 wherein the organic solvent is selected from the group consisting of propyleneglycol methyl ether acetate, ethyl lactate, methyl 3-methoxypropionate, ethyl 3-ethoxypropionate and cyclohexanone.

Claim 12 (original) The photoresist composition of claim 3 wherein the organic solvent is present in a range of from about 100 % to about 1000% by weight of the photoresist polymer.

Claims 13-20 (previously canceled)